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Thermal and photochemical oxidation of self-assembled monolayers on alumina particles exposed to nitrogen dioxide

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Alumina is an important component of airborne dust particles as well as of building materials and soils found in the tropospheric boundary layer. While the uptake and reactions of oxides of nitrogen and their photochemistry on alumina have been reported in the past, little is known about the chemistry when organics are also present. Fourier transform infrared (FTIR) spectroscopy at ~ 23 °C was used to study reactions of NO₂ on γ -Al₂O₃ particles that had been derivatized using 7-octenyltrichlorosilane to form a self-assembled monolayer (SAM). For comparison, the reactions with untreated γ -Al₂O₃ were also studied. In both cases, the particles were exposed to water vapor prior to NO₂ to provide adsorbed water for reaction. As expected, surface-bound HONO, NO₂⁻, and NO₃⁻ were formed. Surprisingly, oxidation of the organic by surface-bound nitrogen oxides was observed in the dark, forming organo-nitrogen products identified as nitronates (R₂C=NO₂⁻). Oxidation was more rapid under irradiation ($\lambda > 290$ nm) and formed organic nitrates and carbonyl compounds and/or peroxy nitrates in addition to the products observed in the dark. Mass spectrometry of the gas phase during irradiation revealed the production of NO, CO₂, and CO. These studies provide evidence for oxidation of organic compounds on particles and boundary layer surfaces that are exposed to air containing oxides of nitrogen, as well as new pathways for the formation of nitrogen-containing compounds on these surfaces.

Introduction

Mineral dust mobilized by dust storms in arid regions constitutes the largest mass fraction of aerosols in the atmosphere.^{1–3} Due to its abundance in the atmosphere, dust plays an important role in climate, visibility, and human health.^{1–6} In addition, the high surface area associated with mineral dust, which is mainly comprised of SiO₂, Al₂O₃, and trace elements,³ provides sites for heterogeneous reactions that can significantly alter the chemical composition and toxicity of the aerosols, and affects the gas-phase composition of the atmosphere through the adsorption of gases.⁷ Building materials and soils have many components common to mineral dust,⁸ and hence similar chemistry is expected on boundary layer surfaces.

Oxides of nitrogen are known to adsorb to and react on mineral oxides.^{9–14} For example, it has long been recognized that NO₂ hydrolysis occurs on such surfaces to form surface nitrite and nitrate ions,^{3,13,15–18} both of which photolyze to generate OH radicals and NO or NO₂.^{17,19–23} This chemistry leads to the release of highly photochemically labile gases such as HONO, a major OH source in the troposphere.^{24–27} Consistent with the results of laboratory studies, increased HONO levels have been measured during dust storms.²⁸ Organic compounds are also known to be taken up on

airborne dust particles^{4,9,29–31} and on building materials in the boundary layer,^{32–37} and there is evidence that oxidation of organics occurs on these surfaces as well.^{33,38,39}

A number of the well-known surface-bound nitrogen oxides such as nitrite and nitrate ions photolyze in the actinic region²⁴ above 290 nm to form O⁻ radical anions, which react with water to generate OH radicals.^{19,20} It has been shown in recent studies^{39–41} that this generation of OH on the surface can lead to oxidation of adsorbed organics, *i.e.*, oxidation from the “bottom up” as compared to the commonly accepted mechanism of oxidation from the “top down” by gases such as O₃, OH and NO₃.^{24,42–45} Given the simultaneous presence of organics and oxides of nitrogen on the surfaces of mineral dust, soils and building materials, it is likely that similar photochemically-driven oxidations of the adsorbed organics could occur from the “bottom up.”

In the present work, self-assembled monolayers (SAM) of a terminal alkene, 7-octenylsilyl groups, were attached to alumina (γ -Al₂O₃) particles as a model system for organic coatings on suspended mineral dust and boundary layer surfaces. Aluminium oxide was chosen as a substrate because of its natural abundance in mineral dust³⁰ and building materials,^{8,24} its affinity for nitrogen oxides, and the ease of functionalizing the Al₂O₃ surface with unsaturated organosilane self-assembled layers of known composition.^{46,47} The surface reactions were studied using Fourier transform infrared spectroscopy, while mass spectrometry was used to monitor gas-phase products formed by photolysis. It is shown that the surface-bound organic layer is oxidized not only during irradiation, but surprisingly, also in the dark. The atmospheric implications of these unusual findings are discussed.

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Experimental

Preparation of SAMs on alumina

Alumina (γ - Al_2O_3 , Inframat Advanced Materials, 99.99 + %) was first heated to 475 °C for 12 h to remove organic impurities and immediately upon cooling, was derivatized with 7-octenylsilyl groups [$\text{H}_2\text{C}=\text{CH}(\text{CH}_2)_6\text{SiO}_3$], designated hereafter as C8=. A stirred suspension of 100 mg of γ - Al_2O_3 in 25 mL of hexadecane was reacted with 7-octenyltrichlorosilane (0.25 mL, Sigma-Aldrich, 96%). The solid was rinsed four times using HPLC grade dichloromethane followed by vigorous shaking and centrifugation to remove unreacted dissolved starting material, and then final centrifugation used to isolate the solid. The residual solvent was removed under a gentle stream of nitrogen followed by evacuation at $\sim 10^{-4}$ Torr for 3 h. The underivatized alumina powder was verified as consisting exclusively of the γ -phase by X-ray diffraction (XRD).

Brunauer-Emmett-Teller (BET) surface areas⁴⁸ of derivatized and underivatized γ - Al_2O_3 substrates were determined by measuring nitrogen adsorption with an Autosorb-1 surface area analyzer (Quantachrome Instruments). Functionalization of the alumina particles with C8= resulted in a 28% reduction in surface area, from 167 ± 3 to 121 ± 4 $\text{m}^2 \text{g}^{-1}$ (2σ). The surface coverage of C8= on one gram of alumina was estimated using the surface area (SA) of untreated alumina powder and the fractional organic carbon content of the derivatized particles [$f_{\text{OC}} = 10.1 \pm 0.3\%$ (2σ), determined by thermogravimetric analysis] according to eqn (I),

$$\text{surface coverage (molecules cm}^{-2}\text{)} = \frac{f_{\text{OC}} \cdot m \cdot N_A}{MW_{\text{C8=}} \cdot SA} \quad (\text{I})$$

where N_A is Avogadro's number, $MW_{\text{C8=}}$ is the molecular weight of an octenylsilane group (187 g mol^{-1}), m is the mass of the alumina substrate (1 g), and SA is the surface area of a gram of derivatized substrate (121 m^2). This gives a surface coverage of $\sim 2 \times 10^{14}$ molecules cm^{-2} . The surface $-\text{OH}$ concentration of γ - Al_2O_3 heated to 500 °C for 12 h, similar to the thermal pretreatment of alumina used here, has been reported⁴⁹ to be $3.6 \times 10^{14} \text{ cm}^{-2}$. Thus, approximately half of the surface $-\text{OH}$ groups have the C8= functional groups and, although the organic coating reduces the gas-accessible alumina surface area, regions of incomplete coverage remain where gases are able to access the Al_2O_3 surface.

FTIR/MS Measurements

Experiments were conducted in a vacuum system equipped with a Fourier transform infrared (FTIR) spectrometer and a mass spectrometer (MS).¹⁷ Samples of alumina particles coated with SAMs were pressed into a fine tungsten grid and mounted on a copper sample holder that enables precise temperature control between cryogenic temperatures and > 1000 K. The sample holder is housed in a stainless steel cube connected to a gas-handling manifold. A quartz fiber optics cable is used to irradiate the sample with light from an externally mounted high pressure Hg-arc lamp (Spectra Physics, Oriel 100 W); a dichroic mirror placed between the lamp and the fiber optics assembly minimizes heating of the sample by

infrared radiation from the lamp. The spectrum of the photolysis light source consists of wavelengths greater than 290 nm, with a maximum between 350 and 450 nm. The FTIR spectrometer (Nicolet Magna 740) is equipped with a liquid nitrogen-cooled Hg-Cd-Te detector. Single beam spectra of the background and those collected during the reaction were obtained from the average of 64 interferograms at a resolution of 4 cm^{-1} . The mass spectrometer (UTI 100C) is attached to the sample chamber *via* leak and gate valves and uses electron ionization (EI) with a quadrupole mass analyzer. This system allows for simultaneous monitoring of species adsorbed to the substrate *via* FTIR as well as gas-phase reactants and products using a leak valve. Samples were irradiated continuously during FTIR experiments and in 40 s intervals for experiments designed to detect gaseous photolysis products with mass spectrometry.

The relative intensity of the lamp emission as a function of wavelength was measured using a spectrofluorometer (FluoroLog, HORIBA Jobin-Yvon), and placed on an absolute intensity scale using the photoisomerization of 2-nitrobenzaldehyde to 2-nitrosobenzoic acid ($\Phi = 0.5$) as a chemical actinometer.⁵⁰ Samples were prepared by mixing 0.5 g of γ - Al_2O_3 with 0.02 g of 2-nitrobenzaldehyde (Sigma-Aldrich, 98%), pressing ~ 10 mg of the mixture into a fine tungsten grid and then irradiating under the same conditions used in the $\text{NO}_x/\text{H}_2\text{O}/\text{C8=}/\gamma\text{-Al}_2\text{O}_3$ photochemistry experiments. Formation of nitrosobenzoic acid in the substrate was followed by FTIR. Using this method, the total absolute intensity over the 290–400 nm region was 2.2×10^{19} photons $\text{cm}^{-2} \text{ s}^{-1}$.

Results

Fig. 1 shows the infrared spectrum of the C8= SAM on alumina using a spectrum of uncoated alumina as the background. The absorptions are similar to previous measurements of alkylsiloxane SAMs on silica.^{51,52} The most prominent peaks at 2927 and 2858 cm^{-1} are due to the asymmetric and symmetric C–H stretching modes [$\nu_{\text{as}}(\text{CH}_2)$ and $\nu_{\text{s}}(\text{CH}_2)$] of the C8= methylene groups, while weaker bands attributed to CH_2 scissoring vibrations of the methylene groups occur between 1470 and 1440 cm^{-1} .⁵³ The terminal alkene gives rise to a vinyl =C–H stretch at 3082 cm^{-1} and a sharp band at 1643 cm^{-1} from the C=C stretch.⁵³ There is also a

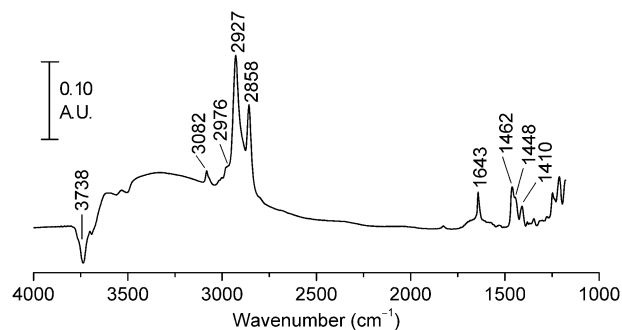


Fig. 1 Fourier transform infrared spectrum of the C8= SAM on γ - Al_2O_3 powder using the underivatized powder as the background spectrum.

weak $=\text{CH}_2$ stretching vibration at 2976 cm^{-1} and a band at 1410 cm^{-1} from an in-plane deformation vibration (scissoring) of the $=\text{CH}_2$ group.⁵³ The disordered nature of the C8 = chains in the SAM is revealed by the position and peak width of the CH_2 stretches shown in Fig. 1.^{52,54} The $\nu_{\text{as}}(\text{CH}_2)$ of C8 = on alumina particles at $\sim 2927\text{ cm}^{-1}$ is shifted by $+12\text{ cm}^{-1}$ and the full-width at half maximum (fwhm) is $\sim 20\text{ cm}^{-1}$ wider than the $\nu_{\text{as}}(\text{CH}_2)$ of a C18 alkane (ordered) film on a flat silica substrate.^{52,54} A broad feature between $3600\text{--}2500\text{ cm}^{-1}$ is likely due to small amounts of adsorbed water, while the sharp negative peak at 3738 cm^{-1} is a surface O–H stretch⁵⁵ that decreases due to reaction with the C8 = trichlorosilane groups. Additional decreases in surface –OH absorptions occur when the C8 = SAM is exposed to water vapor (not shown), indicating that some surface –OH groups remain after coating and are available for interaction with gases.

Reactions of NO_2 on $\gamma\text{-Al}_2\text{O}_3$ particles with and without the C8 = were first studied in the dark. Prior to sequential exposure of the sample to doses of NO_2 , the $\gamma\text{-Al}_2\text{O}_3$ particles (either derivatized or untreated) were exposed to water vapor and subsequently evacuated for 30 min in order to provide surface-adsorbed water for the NO_2 hydrolysis. Chemisorption of nitrogen oxides on alumina is known to give a complex variety of adsorbed nitrite and nitrate species.^{3,13,14,17,18,56,57} The amount of NO_2 that the substrate was exposed to was chosen to optimize the concentration of surface-adsorbed nitrite compared to nitrate. At higher NO_2 doses, nitrite is converted to nitrate *via* reaction (1):¹⁷

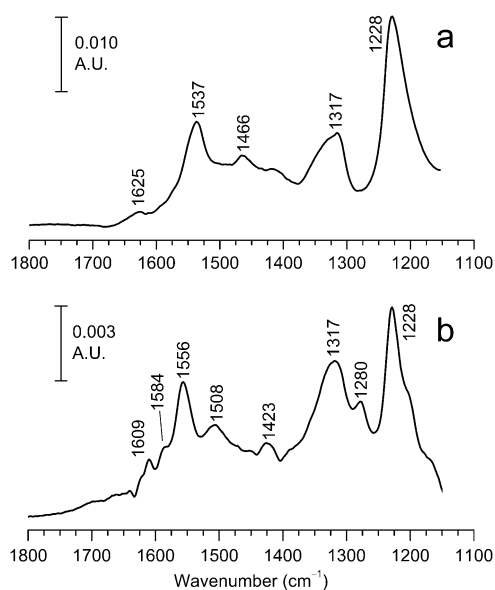


Fig. 2 (a) Infrared spectrum of $\gamma\text{-Al}_2\text{O}_3$ after exposure to H_2O and followed by addition of 45 mTorr NO_2 ; (b) spectrum of C8 = derivatized $\gamma\text{-Al}_2\text{O}_3$ that was previously exposed to H_2O after addition of 45 mTorr NO_2 . Both spectra used the single beam spectrum just before the addition of NO_2 as the reference so that only changes due to the NO_2 reactions are seen.

Fig. 2a shows the spectrum of an underivatized alumina sample in the presence of NO_2 . The spectrum is referenced to the single beam spectrum just before the addition of NO_2 , so the observed changes are due solely to the uptake and reactions of the gas. Based on previous studies of species formed from exposure of Al_2O_3 to NO_2 ,^{3,12–14,17,18,56–59} the peaks at 1625, 1537, and 1317 cm^{-1} are assigned to surface-bound NO_3^- , and that at 1466 cm^{-1} to surface-bound NO_2^- . The strongest peak at 1228 cm^{-1} is assigned to surface-bound HONO.¹⁷ This assignment is supported by previous observations of the formation of HONO on Al_2O_3 ,¹⁷ by its loss during photolysis (see below) and by an accompanying broad weak peak near 3500 cm^{-1} in the O–H stretching region (not shown), which is expected for HONO.^{60,61}

Fig. 2b shows the analogous spectrum for the C8 = SAM on alumina exposed to NO_2 . Peaks due to HONO (1228 cm^{-1}) and NO_3^- ($1317, 1556\text{ cm}^{-1}$) are again formed but are less intense as expected if the Al_2O_3 was partially protected by the SAM. New peaks appear at 1280, 1423, 1508, 1584, and 1609 cm^{-1} , and there are small decreases in peaks in the 3000 cm^{-1} region due to losses of CH_2 and $=\text{CH}_2$ groups (not shown). The region of the spectrum between 1100 and 1600 cm^{-1} is quite congested with absorptions due to nitrate bound in various ways to the surface (monodentate, bidentate and bridging).^{12,17,56} However, the new peaks at 1280, 1584, and 1609 cm^{-1} are only observed in the presence of the organic, and track each other with time (*i.e.*, their ratios remain constant), suggesting that they are due to organic products formed by reaction of surface-bound oxides of nitrogen with the C8 = moiety.

After the spectrum in Fig. 2b was obtained, the cell was pumped out and spectra were collected over time to monitor the sample's stability in the dark under vacuum. Fig. 3a shows the changes in the spectra over the course of an hour. The peak due to surface HONO (at 1228 cm^{-1}) decreases and peaks at 2262, 1607, 1584, 1528, 1425, 1280, and 1165 cm^{-1} grow in. While the reaction is slow, it is remarkable that it occurs in the dark at all. The small peak at 2262 cm^{-1} is too small to follow quantitatively, but it appears to also be associated with peaks due to the organic products.

Fig. 3b shows the changes of the sample in Fig. 3a during irradiation with filtered light ($\lambda > 290\text{ nm}$) over a period of 7 h. A partial pressure of 100 mTorr of O_2 was maintained to propagate alkoxy and peroxy radical pathways that occur under atmospheric conditions.²⁴ The spectra are the ratio of the single beam spectra of the C8 = derivatized alumina/ $\text{H}_2\text{O}/\text{NO}_x$ sample at various irradiation times to that of the sample prior to irradiation. Loss of surface-bound HONO and the formation of product peaks that are similar to those formed in the dark (Fig. 3a) are observed, but appear at a faster rate. A comparison of the rates of increase in the intensity of the peak at 1280 cm^{-1} and loss of the peak at 1228 cm^{-1} shows that the photochemical reactions are enhanced by a factor of two relative to those occurring in the dark. In addition, there is an intense peak at 1638 cm^{-1} that we assign to an organic nitrate (RONO_2),⁵³ a peak at 1700 cm^{-1} (discussed below), and a broad peak around 3200 cm^{-1} assigned to adsorbed water.⁵² The shape

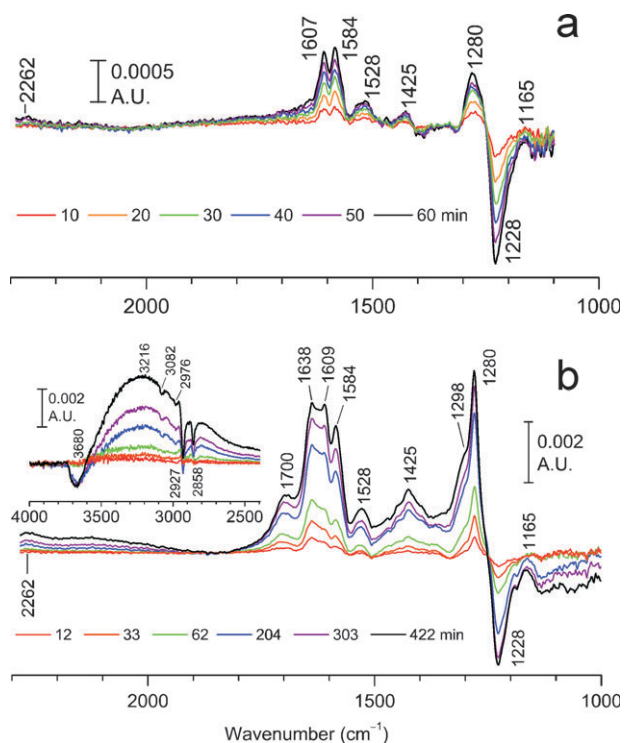


Fig. 3 (a) Changes in the infrared spectrum of the SAM-coated Al_2O_3 that had been reacted with NO_2 (Fig. 2b) after pumping out the NO_2 . The reference is the first spectrum taken after evacuating the cell, so that changes due to the thermal reaction in the dark are seen; (b) changes in the spectrum of the sample in (a) during photolysis ($\lambda > 290$ nm, $P_{\text{O}_2} = 100$ mTorr). The reference spectrum was taken immediately before irradiation to emphasize changes due to photolysis.

of the peaks in the $1550\text{--}1700$ cm^{-1} region suggests there is also an underlying broad peak, likely due to the bending vibration in water. Peaks due to $-\text{CH}_2-$ and $=\text{CH}_2$ decrease, but it is noteworthy that the loss of CH_2 is large relative to loss of the $=\text{C}-\text{H}$ stretch, suggesting that reaction of the double bond is not the sole, nor necessarily the primary reaction pathway. The negative peak at 3680 cm^{-1} is due to a loss of free surface $-\text{OH}$ groups that become involved in hydrogen bonding with water formed during photolysis.

The gas phase products generated during photolysis of C8= derivatized alumina that had been exposed to $\text{H}_2\text{O}/\text{NO}_2$ were monitored using mass spectrometry. Fig. 4a shows that during irradiation, gas phase products with peaks at m/z 30, 44 and 28 were formed. It is noteworthy that there was no detectable peak at m/z 46; however, the mass spectrum of an authentic sample of NO_2 under these conditions did not have a strong peak at m/z 46, so that its yield in the present case is uncertain. While these peaks cannot be assigned with certainty with low resolution mass spectrometry, it is likely that they are due to NO , CO_2 and CO , respectively. A significant contribution from HCHO at m/z 30 and 28 is ruled out by the absence of a peak at m/z 29.⁶² These gases are not observed when the sample is heated ($+0.7$ K) in the dark (see Fig. 4b, between 400–600 s), so the evolution of NO , CO_2 , and CO is not an artifact of the substrate being heated ($+0.3$ K) during irradiation.

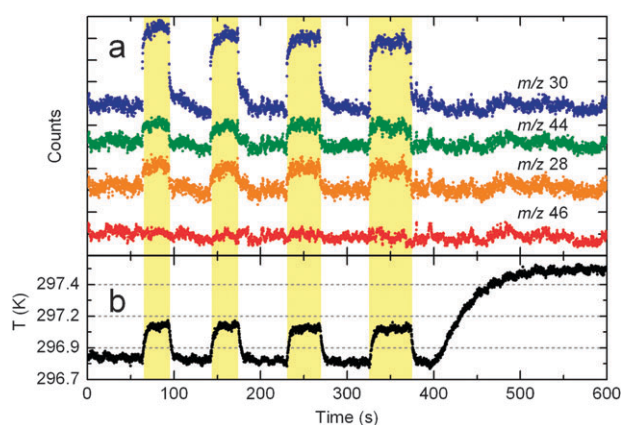
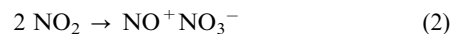


Fig. 4 (a) Changes in peaks in mass spectrum at m/z 30 (NO), 28 (CO), 44 (CO_2) and 46 (NO_2) induced by photolysis (yellow bars) at $\lambda > 290$ nm of a C8= SAM on $\gamma\text{-Al}_2\text{O}_3$ that was previously exposed to H_2O and NO_2 . (b) Changes in the sample temperature during photolysis. The sample is irradiated here in 40 s intervals to demonstrate repeatability of the measurement.

Discussion

While there have been a number of studies of the uptake and reactions of NO_2 on alumina both in the absence and presence of water,^{3,12–15,17,18,56–59,63} we are unaware of any study in which a SAM-derivatized alumina substrate was exposed to NO_2 . Although perfectly ordered SAMs may provide an effective barrier between the gas-phase and the substrate, previous studies have shown that gases may penetrate between the hydrocarbon chains,^{64,65} especially at the edges of defects and islands of a rough substrate. The C8= coverage is expected to be irregular on Al_2O_3 particles, exposing more of the substrate to gases compared to well-organized alkane SAMs on silica or gold, for example. In addition, as discussed above the surface concentration of the C8= SAM corresponds to approximately 50% of the initial available surface $-\text{OH}$ groups on the Al_2O_3 . This partial coverage, combined with the positions and widths of the $-\text{CH}_2-$ bands indicating the SAM is relatively disordered, suggests that the Al_2O_3 surface will be accessible to the NO_2 after derivatization.

When NO_2 is taken up by a surface, particularly on metal oxides such as Al_2O_3 , surface ions are formed,



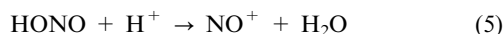
where the NO^+ becomes associated with the surface oxide anions and the NO_3^- with the surface aluminium cations. In the gas phase, water aids in this ionization⁶⁶ and the same is likely true on surfaces. In addition, water reacts with the $\text{NO}^+ \text{NO}_3^-$ ion pair to form nitrous and nitric acids:^{16,67–70}



Nitrous acid can dissociate on the oxide surface to generate nitrite ions,



just as HNO_3 dissociates to form NO_3^- . Under sufficiently acidic conditions, protonation to generate NO^+ also occurs:

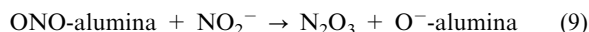


Reactions (2)–(5) are consistent with the formation of surface-bound NO_2^- , NO_3^- , and HONO , as seen in Fig. 2a and reported in previous studies.^{3,12–14,17,56–58}

The formation of additional products with peaks at 1280, 1584, and 1609 cm^{-1} when the C8 = SAM is present, accompanied by a decrease in the $-\text{CH}_2-$ and $=\text{CH}$ peaks (Fig. 2b), indicate that some of the surface-bound products of the NO_2 chemistry react with the attached organic. Since this occurs in the dark as well as upon photolysis, the oxidizing species that initiates the chemistry is likely to be one or more of the intermediates and/or products in Reactions (2)–(4). We propose that NO^+ initiates the oxidation *via* two pathways: addition of NO^+ to the double bond directly, or conversion of NO^+ to N_2O_3 , which in turn adds to the double bond,⁷¹



where R represents any organic group. By analogy to aqueous systems, the mechanism of dinitrogen trioxide formation in these experiments can stem from the reaction of NO^+ with basic surface sites on alumina to form an adsorbed nitrito species, which subsequently reacts with nitrite ion to give N_2O_3 :⁷¹

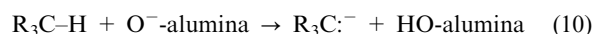


While adsorbed N_2O_3 was not observed in experiments when H_2O was present, an appreciable amount (indicated by a broad band centered at 1950 cm^{-1}) did form during exposures

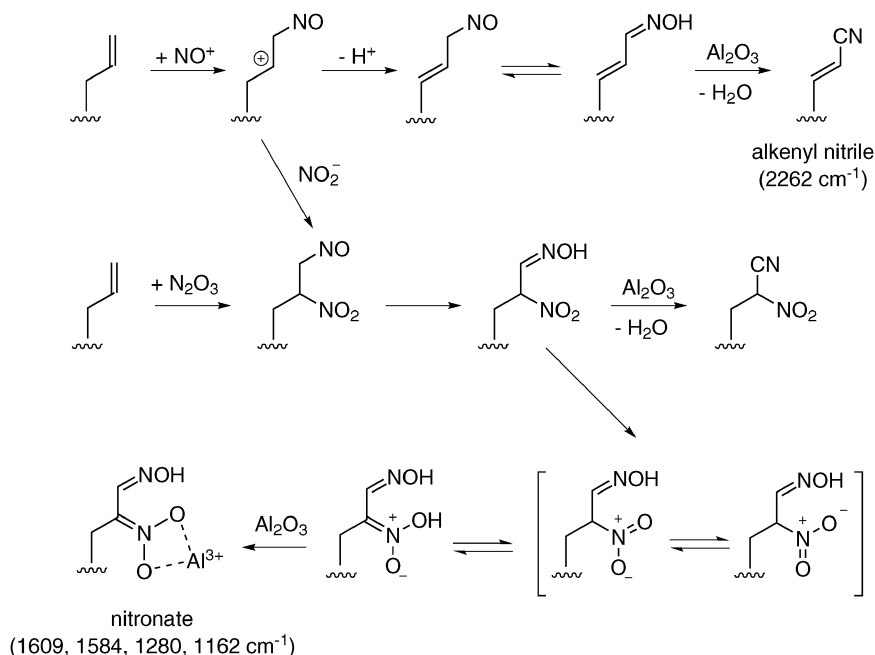
of alumina to NO_2 under dry conditions, in agreement with previous studies.¹⁷

The carbocations formed in reaction (6) may undergo a number of reactions, including the addition of anions or the elimination of a proton to generate an alkene.⁷² Scheme 1 shows a sequence of reactions that leads to the formation of a nitro group ($\text{R}_2\text{C}-\text{NO}_2$) which is a precursor to a nitronate ($\text{R}_2\text{C}=\text{NO}_2^-$)^{72,73} that is likely chelated to Al^{3+} sites on the surface. Nitronates are known to have strong peaks that correspond to the 1280, 1584 and 1609 cm^{-1} bands observed here.^{53,74} As shown in Scheme 1, addition of NO^+ to a double bond forms a nitroso compound ($\text{R}_2\text{C}-\text{NO}$) that can generate a nitrile ($\text{RC}\equiv\text{N}$) *via* dehydration of an oxime intermediate; the stretching vibration of the $-\text{C}\equiv\text{N}$ group is typically in the range of 2200–2600 cm^{-1} , and we assign the weak peak at 2262 cm^{-1} (Fig. 3a,b) to a nitrile.^{53,75} While peaks in the 2250 cm^{-1} range have been assigned to NO^+ in previous studies,^{17,68–70,56,76} the peak at 2262 cm^{-1} only appeared when the organic coating was present, suggesting it is likely due to an organic product such as a nitrile. It is also possible that this peak belongs to an isocyanate (RNCO) species.^{77,78} However, it is not possible to distinguish between these two possibilities spectroscopically, but mechanistically, the formation of nitriles is more reasonable.

An alternative mechanism for the formation of nitroso-organic products may be the activation of a methylene group by its interaction with a basic site on the alumina surface. The resulting carbanion may then be nitrosated by NO^+ on the surface.^{71,72}



The formation of allylic carbanions coordinated to Al^{3+} in tetrahedral vacancies has been observed in studies of propene

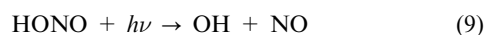


Scheme 1 Thermal reactions leading to organo-nitrogen products.

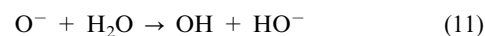
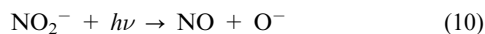
on alumina or other metal oxide surfaces.^{79–81} It is also possible that the proximity of the hydrocarbon chain to acidic sites on the alumina surface could promote reactions leading to carbocations that react similarly to those formed in reaction (6).^{82–84} In short, the products formed in Fig. 3a are likely a result of alumina-mediated reactions such as (6)–(11) that activate the hydrocarbon chain toward reaction with adsorbed NO_x species.

While there is evidence from solution phase reactions that the ion pair NO^+NO_3^- reacts with alkenes to give organo-nitrosnitrates,^{85,86} this should lead to a strong absorption band in the 1615–1660 cm^{-1} region due to the asymmetric NO_2 stretch as well as in the 1250–1300 cm^{-1} region due to the symmetric NO_2 stretch. While there is a strong band at 1280 cm^{-1} in Fig. 3a, a band in the asymmetric NO_2 region only appears after photolysis (see below). Hence direct reaction of the ion pair with the alkene seems unlikely in the present experiments, perhaps due to separation of the ions and their strong adsorption on the alumina surface.

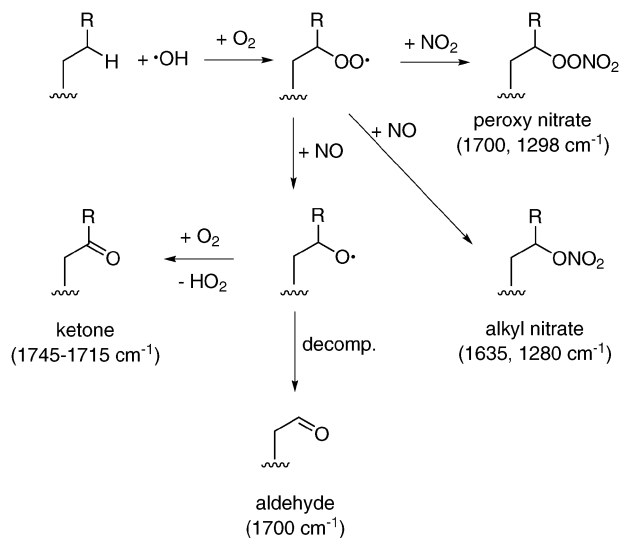
During photolysis, the band at 1228 cm^{-1} assigned to HONO decreases as expected since HONO is known to photolyze rapidly²⁴ to generate OH and NO:



Nitrite ions also photolyze above 300 nm^{19,20} and form OH radicals if water is available:



In either case, NO is generated, which accounts for the mass spectral peak at m/z 30 during irradiation (Fig. 4a). From diffuse reflection UV-vis absorption measurements it was previously reported that the $\pi^* \leftarrow n$ transition of nitrate adsorbed to alumina surfaces is centered at 275 nm,¹³ blue-shifted from 310 nm observed for aqueous sodium nitrate.¹⁹ Thus, there is poor overlap of the lamp emission spectrum with the absorption spectrum of adsorbed nitrate. This is



Scheme 2 Mechanism of C8= photooxidation on alumina in the presence of adsorbed NO_x .

consistent with our observation that nitrate does not photolyze further under the conditions of these experiments.

Scheme 2 shows the mechanism of oxidation of the alkyl chain initiated by OH, which leads to the formation of organic nitrates, peroxy nitrates, aldehydes, and ketones. The peak at 1638 cm^{-1} that appears in the photolysis experiments (Fig. 3b) is assigned to RONO_2 ,^{53,87} and is accompanied by a peak at 1280 cm^{-1} , which is overlapped by that from nitronate species. The combination of peaks at 1700 cm^{-1} and 1298 cm^{-1} suggests formation of a peroxy nitrate (ROONO_2),⁸⁷ although as discussed below, there may be a contribution from a carbonyl group at 1700 cm^{-1} .

While OH radicals may attack at either the terminal alkene group or along the alkyl chain, the relatively small loss of the $=\text{CH}_2$ moiety (Fig. 3b) suggests that the alkyl chain is the main point of attack *via* H-abstraction. This is not surprising since the $\text{C}=\text{C}$ group is at the far end of the chain, distant from the surface that generates and holds the reactive intermediates. Similar conclusions were reached by Karagulian *et al.*⁴¹ in their studies of the photooxidation of partially saturated phospholipids adsorbed to $\text{NaCl}/\text{NaNNO}_2$ salt mixtures.

The production of gas phase CO and CO_2 (Fig. 4a) is somewhat surprising. Although oxidation of hydrocarbons will lead to these products and has been observed in the reaction of gas-phase O_3 and OH with organic self-assembled monolayers on quartz,^{88–90} it requires a number of secondary reactions. However, here the experiments show that CO and CO_2 are generated immediately on photolysis. We have observed in unrelated studies that O_3 is generated from photolysis of as-of-yet unidentified oxides of nitrogen bound to stainless steel surfaces. If O_3 were also generated in the present system, oxidation of the double bond would lead to an aldehyde and a one-carbon Criegee intermediate HCHOO , which is known to decompose to CO and CO_2 .²⁴ In this case, the 1700 cm^{-1} infrared band (Fig. 3b) may also include a contribution from aldehydes arising from ozonolysis reactions.

Atmospheric implications

Hydrocarbons are oxidized by surface-bound oxides of nitrogen formed in the uptake and hydrolysis of NO_2 on alumina, which is used here as a proxy for airborne dust, soils, and building materials. This occurs not only during irradiation, but also in the dark at approximately half the rate driven by photolysis. This chemistry will lead to a variety of organonitrogen compounds being formed on dust particles, soils, and building materials, and to the regeneration of gaseous products such as NO, CO, CO_2 and potentially, some small organic molecules generated during the oxidation. The actinometer measurements indicate that in these experiments the light intensity in the 290–400 nm region is about three orders of magnitude larger than that at Earth's surface from an overhead sun.²⁴ Assuming the rate of the photochemical oxidation is proportional to the light intensity, this suggests that the photolysis reactions will be much slower in air than observed here, and that it is the thermal reactions that will actually be more important under atmospheric conditions.

In short, oxides of nitrogen and organics are not only removed by adsorption on the surfaces of airborne dust particles, soils, and building materials, but these surfaces provide a medium for their further reactions, both in the dark and under solar irradiation.

Summary

Gas phase NO₂ reacts with an alkene self-assembled monolayer on γ -Al₂O₃ that had been exposed to water vapor both in the dark and under irradiation with wavelengths above 290 nm. Unique organo-nitrogen products such as nitronates (R₂C=NO₂⁻) and possibly nitriles (e.g., RCH=CHCN) were identified as products in the dark. Under irradiation, organic nitrates and possibly peroxy nitrates and/or carbonyl compounds are formed, and gas-phase NO, CO, and CO₂ are generated. This chemistry suggests that both thermal and photochemical reactions of nitrogen oxides with organics on surfaces should be considered in models of processes occurring in the lower atmosphere.

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